

Symposium (Oral) | Symposium : Novel functional oxide materials, devices, techniques for next generation transistor channel application

📅 Sun. Mar 16, 2025 1:30 PM - 5:40 PM JST | Sun. Mar 16, 2025 4:30 AM - 8:40 AM UTC 🏛️ K203  
(Lecture Hall Bldg.)

**[16p-K203-1~10] Novel functional oxide materials, devices, techniques for next generation transistor channel application**

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5:35 PM - 5:40 PM JST | 8:35 AM - 8:40 AM UTC

[16p-K203-10] For the next 100 years

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Keywords : semiconductor、transistor、oxide

In commemoration of the 100th anniversary of FETs, our symposium is held on topics related to next-generation transistors, focusing on oxide materials. How will transistor technology evolve over the next 100 years? Let's make a bold prediction.

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